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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/669,996	09/24/2003	Ju-Il Lee	29926 /39504	6198	
4743	7590 04/28/2005		EXAMINER		
MARSHALL, GERSTEIN & BORUN LLP			HARRISON, MONICA D		
233 S. WACKER DRIVE, SUITE 6300 SEARS TOWER CHICAGO, IL 60606		00	ART UNIT	PAPER NUMBER	
			2813		

DATE MAILED: 04/28/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)	
	10/669,996	LEE, JU-IL	
Office Action Summary	Examiner	Art Unit	
	Monica D. Harrison	2813	
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet with the c	orrespondence address	
A SHORTENED STATUTORY PERIOD FOR REPL THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1. after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a rep If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailine earned patent term adjustment. See 37 CFR 1.704(b).	136(a). In no event, however, may a reply be tirely within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).	
Status	·		
<ul> <li>1) Responsive to communication(s) filed on <u>02 F</u></li> <li>2a) This action is FINAL. 2b) This</li> <li>3) Since this application is in condition for allowed closed in accordance with the practice under</li> </ul>	s action is non-final. ance except for formal matters, pro		
Disposition of Claims			
4) Claim(s) 1-4 and 9 is/are pending in the application 4a) Of the above claim(s) is/are withdrates 5) Claim(s) is/are allowed.  6) Claim(s) 1-4 and 9 is/are rejected.  7) Claim(s) is/are objected to.  8) Claim(s) are subject to restriction and/	awn from consideration.		
Application Papers			
9) The specification is objected to by the Examin 10) The drawing(s) filed on is/are: a) ac Applicant may not request that any objection to the	cepted or b) objected to by the drawing(s) be held in abeyance. Se	e 37 CFR 1.85(a).	
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	•		•
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for foreig  a) All b) Some * c) None of:  1. Certified copies of the priority document  2. Certified copies of the priority document  3. Copies of the certified copies of the priority application from the International Bureat  * See the attached detailed Office action for a list	nts have been received. Its have been received in Applicat ority documents have been receive au (PCT Rule 17.2(a)).	ion No ed in this National Stage	
	•		
Attachment(s)  1) Notice of References Cited (PTO-892)	4) 🔲 Interview Summary	(PTO-413)	
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D		
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date	6) Other:		

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#### **DETAILED ACTION**

1. Applicant's amendment filed 2/2/05 has been entered. Examiner acknowledges claims 5-8 and 10-11 have been withdrawn.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 3, 4, and 9 are rejected under 35 U.S.C. 102(b) as being anticipated by Yang et al (6,180, 969 B1).

2. Regarding claim 1, Yang et al discloses a method for fabricating a CMOS image sensor including a low voltage buried photodiode and a transfer transistor, the method comprising: a) forming a field oxide (Figure 7C, reference 707) for defining an active area and a field area (column 7, lines 14-17) on a certain area of an epitaxial layer (Figure 7C, reference 702) formed on a substrate (Figure 7C, reference 701), and forming a gate (Figure 7D, reference 711) of a transfer transistor (column 7, lines 34-39) on the epitaxial layer of the active area, b) forming a low voltage buried photodiode doping region in alignment with one side of the gate of the transfer transistor (Figure 7I, reference LVPD); c) forming a spacer insulation layer by stacking layers of oxide and nitride over the whole structure (Figure 7C; reference 706); d) forming a spacer block mask (Figure 7I, reference 727) on the spacer insulation layer to open areas opposite the transfer transistor from the low voltage buried photodiode doping region while leaving the photodiode doping region covered by the spacer insulation layer and spacer block

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mask (Figure 7I); and removing the spacer insulation layer not covered by the spacer block mask to form a spacer on a sidewall of the transistor, removing the spacer block masks forming a second mask over the portion of the spacer insulation-layer remaining on the photodiode doping region and leaving the area opposite the transistor open (Figure 7I), and forming a floating diffusion region on the open area opposite the transfer transistor from the photodiode doping region while the second mask and the remaining portion of the space insulation layer is in place over the photodiode doping region (Figures 7I and 7J).

- Regarding claim 3, Yang et al discloses wherein part b) further comprises: sequentially performing n-type ion implantation and p-type ion implantation using a first mask with an opening disposed over the low voltage buried photodiode doping region (column 6, lines 63-67 thru column 7, lines 1-13; Figure 7A, reference 703).
- 4. Regarding claim 4, Yang et al discloses wherein the spacer block mask of part d) is formed using the first mask of part b) and a negative photoresist (Figure 4, reference 41).
- 5. Regarding claim 9, Yang et al discloses a CMOS image sensor made in accordance with the method of claim 1 (Figures 7A-7I).

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 2 is rejected under 35 U.S.C. 103(a) as being unpatentable over Yang et al (6,180,969 B1) in view of Rhodes 6,611,037 B1).

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6. Yang et al discloses all above claimed subject matter except wherein the oxide layer of the spacer insulation layer has a thickness ranging from about 200 Angstroms to about 2000 Angstroms, and the nitride layer of the spacer insulation layer has a thickness ranging from about 200 Angstroms to about 1000 Angstroms.

Rhodes discloses wherein the oxide layer and nitride layer of the spacer insulation layer has a thickness ranging from about 20 Angstroms to about 500 Angstroms however, Rhodes does not teach the specified parameters for the layers of claim 2.

It would have been obvious, at the time the invention was made, for one with ordinary skill in the art, to provide a oxide layer of the spacer insulation layer has a thickness ranging from about 200 Angstroms to about 2000 Angstroms, and the nitride layer of the spacer insulation layer has a thickness ranging from about 200 Angstroms to about 1000 Angstroms, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the "optimum range" involves only routine skill in the art. *In re Aller*, 105 USPQ 233, 1955.

#### Response to Arguments

7. Applicant's arguments with respect to claims 1-4 and 9 have been considered but are most in view of the new ground(s) of rejection.

### Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Monica D. Harrison whose telephone number is 571-272-1959. The examiner can normally be reached on M-F 7:00am-3:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Monica D. Harrison AU 2813

> CRAIG A. THOMPSON PRIMARY EXAMINER

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mdh

April 22, 2005

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